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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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of

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Complete if Known

Application Number

09/699,614

Filing Date

10/30/2000

First Named Inventor

Silver

Group Art Unit

2621

Examiner Name

Not Known

Attorney Docket Number

C00-057 Technology Center 2600

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

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**Examiner
Signature**

Date
Considered

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**INFORMATION DISCLOSURE
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Sheet

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of

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Complete if Known

Application Number 09/699,614

Filing Date 10/30/2000

First Named Inventor Silver

Group Art Unit 2854

Examiner Name Not Known

Attorney Docket Number C00-057

Technology Center 2600

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OCT 23 2001

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Citeq No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
BL		KLA-TENCOR, INC., Candidate Alignment Target For Wafer, 1997	
		DAVID I. HAVERLOCK, Geometric Precision in Noise-Free Digital Images, IEEE Transactions on Pattern Analysis and Machine Intelligence, VOL. II No 10. October 1989	
		JOHN W. HILL, Machine Intelligence Research Applied To Industrial Automation, National Technical Information Service, U.S. Department of Commerce, November 1980	
		CHINMOY B. BOSE AND ISREAL AMIR, Design of Fiducials for accurate Registration Using Machine Visions, IEEE Transaction on Pattern Analysis and Machine Intelligence, VOL. 12 No. 12, December 1990	
		LAWRENCE O'GORMAN, Subpixel Precision of Straight-Edged Shapes for Registration and Measurement, IEEE Transactions on Pattern Analysis and Machine Intelligence, VOL. 18, No. 7 1996	
		H.F. GILLESPIE AND J.E. MARTIN, Optimization of Optical Alignment Marks Through Circuit Design Rule Consideration, Rockwell International, Newport Beach, CA, 1978	
		NEAL T. SULLIVAN, Semiconductor Pattern Overlay, Digital Equipment Corp., Advanced Semiconductor Development	
		HIDEKI INA, KOICHI SENTOKU AND TAKAHIRO MATSUMOTO (Nanotechnology research Center) - HIROAKI SUMITANI AND MUNEOYOSHI SUITA (Advanced Technology R&D Center, Alignment Mark Optimization to Reduce Tool and Wafer Induced Shift for XRA-1000	
		W. MAKOUS, Optimal Patterns For Alignment, Applied Optics Vol. 13, No. 3, March 1974	
		EGIL D. CASTEL and NADER SHAMMA, Design and Optimization of Site-By-Site Alignment Marks for a Single Polysilicon Bipolar Process, National Semiconductor Corporation, Elsevier Science Publishers B.V.	
BL		ALFRED M. BRUCKSTEIN, LARRY O'GORMAN AND ALON ORLITSKY, Design of Shapes for Precise Image Registration, IEEE Transactions on Information Theory, VOL. 44, No. 7, November 1998	

Examiner
Signature

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10/22/03

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